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-05/19 6-25-00 [10191/1711]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor(s) : Volker BECKER et al.
Serial No. : To Be Assigned
Filed : Herewith
For : **DEVICE AND METHOD FOR HIGH-RATE ETCHING A SUBSTRATE USING A PLASMA ETCHING SYSTEM AND DEVICE AND METHOD FOR IGNITING A PLASMA AND ADJUSTING UPWARD OR PULSING THE PLASMA POWER**
Examiner : To Be Assigned
Art Unit : To Be Assigned

Assistant Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

SIR:

Kindly amend the above-identified application before examination as set forth below.

IN THE SPECIFICATION:

On page 1, before line 5, insert: FIELD OF THE INVENTION--

On page 1, line 13, delete "Related Art" and insert: DESCRIPTION OF RELATED ART--

On page 3, line 13, change "German Patent 41 42 045 C1" to German Patent 42 41 045 C1--

On page 4, line 19, insert: SUMMARY OF THE INVENTION--

On page 4, line 28, delete "Advantages of the Invention".